

DISCUSSION OF THE AMENDMENT

Claim 6 has been amended to depend on Claim 1.

No new matter is believed to have been added by the above amendment. Claims 1-15 remain pending in the application.

REMARKS

The rejections under 35 U.S.C. § 102(e) of Claims 1-6 and 10-15 as anticipated by U.S. 2005/0095770 A1 (Kumangi et al); and under 35 U.S.C. § 103(a) of Claims 6 and 12-15 as unpatentable over Kumangi et al in view of U.S. 6,475,902 (Hausmann et al), and Claims 7-11 as unpatentable over Kumangi et al, are respectfully traversed.

The underlying application published as Kumangi et al entered the national stage on July 12, 2004. In addition, the earliest publication of the subject matter disclosed in Kumangi et al was that in JP 2003-282566, published October 3, 2003. Thus, the earliest prior art date of the subject matter of Kumangi et al is October 3, 2003. **Submitted herewith** is a certified English translation of Applicants' Japanese priority application, i.e., Japan 2003-016659, filed June 24, 2003. Applicants respectfully request that the Examiner find that the priority application supports present Claim 1, the sole remaining independent claim. With Kumangi et al eliminated as prior art, Hausmann et al alone neither discloses nor suggests the presently-claimed invention, because Hausmann et al neither discloses nor suggests the combination of hexaethylaminodisilane gas and ammonia gas used in combination with a CVD method for forming a silicon nitride film on a target substrate.

Application No. 10/518,025
Reply to Office Action of September 19, 2005

Applicants respectfully submit that the application is now in immediate condition for allowance. Accordingly, the Examiner is respectfully requested to pass this application to issue.

Customer Number

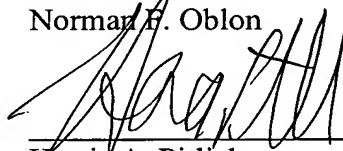
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Tel: (703) 413-3000
Fax: (703) 413 -2220
(OSMMN 06/04)

NFO:HAP\la

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND,
MAIER & NEUSTADT, P.C.
Norman F. Oblon



Harris A. Pitlick

Registration No. 38,779